

*Electronic Supplementary Information for:*

**The Prediction of hole mobility in organic semiconductors and its  
calibration based on the grain-boundary effect**

Jin Woo Park, Kyu Il Lee, Youn-Suk Choi,\* Jung-Hwa Kim, Daun Jeong, Young-Nam Kwon, Jong-Bong Park, Ho Young Ahn, Jeong-Il Park, Hyo Sug Lee\*\* and Jaikwang Shin

*Samsung Advanced Institute of Technology, Samsung Electronics Co. Ltd., 130 Samsung-ro,  
Yeongtong-gu, Suwon-si, Gyeonggi-do 16678, Republic of Korea*

**Table S1** Grain size ( $G$ ) and hole mobilities ( $\mu$  in  $\text{cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ ) of in-house OTFTs according to processing temperature ( $T_{\text{sub}}$  in  $^\circ\text{C}$ ). These data were used in Fig. 5 to develop calibration model

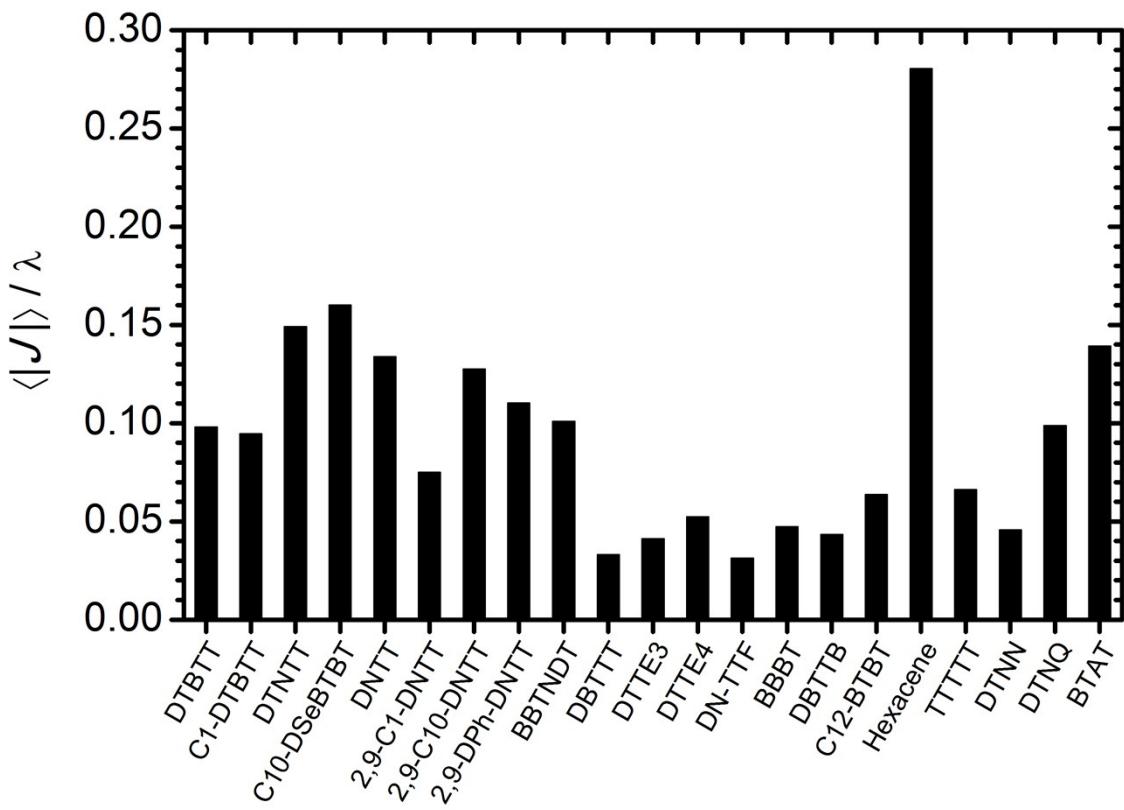
Molecule	$T_{\text{sub}}$	$N_{\text{grain}}^a$	$G^b$	$\mu_{\text{exp}}$	$\mu_{\text{calculated}}$	$\mu_{\text{calibrated}}^c$
<b>1</b> (DTBTT)	25	1540	0.13	2.82	18.9	2.81
	40	174	0.38	6.89		6.15
	60	22	1.07	13.87		10.04
	80	12	1.44	8.26		-
<b>2</b> (C <sub>1</sub> -DTBTT)	80	312	0.28	5.44	21.4	5.79
	100	66	0.62	7.86		9.06
	120	24	1.02	5.13		-
<b>3</b> (DTNTT)	80	106	0.49	4.4	12.9	4.84
	120	25	1.00	6.0		6.70
	160	16	1.25	9.75		7.23
<b>4</b> (C <sub>10</sub> -DSeBTBT)	70	612	0.20	5.6	24.6	5.24
	90	195	0.36	7.3		7.73
	110	78	0.57	8.8		9.98

<sup>a</sup> Number of grains were counted from the AFM images. <sup>b</sup> Average grain size in  $\mu\text{m}$ .

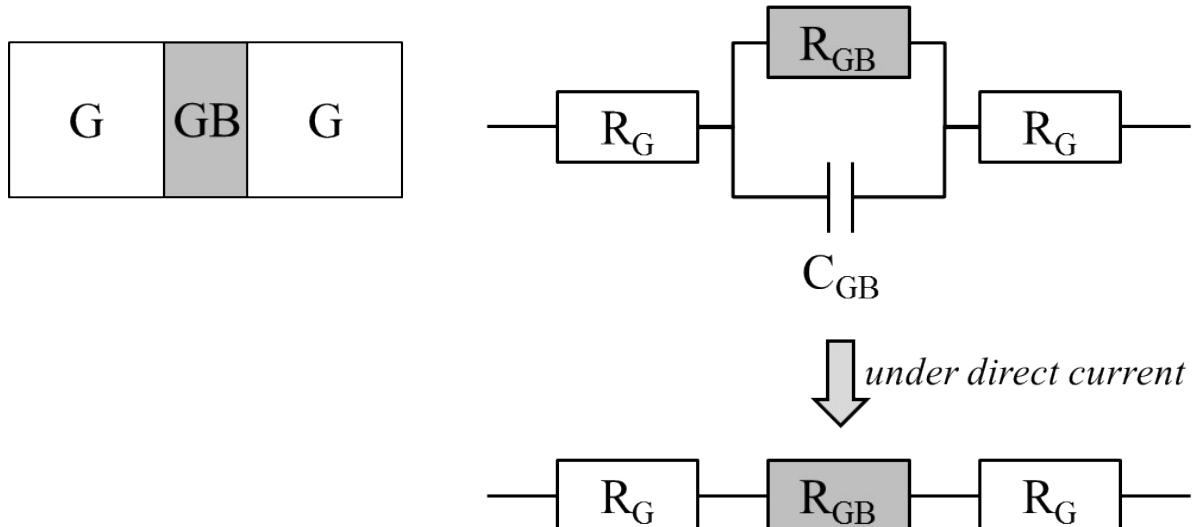
<sup>c</sup> Calibrated using equation (3) in the manuscript. Mobilities beyond the maximum  $\mu_{\text{exp}}$  were not calibrated.

**Table S2** Averaged absolute value of transfer integrals ( $\langle |J| \rangle$ ) between the neighboring pairs in the morphology, reorganization energy ( $\lambda$ ), and their ratio for the organic molecules used in this work.

Molecule	$\langle  J  \rangle$ (eV)	$\lambda$ (eV)	$\langle  J  \rangle / \lambda$
<b>1</b> (DTBTT)	0.01417	0.14425	0.09821
<b>2</b> (C <sub>1</sub> -DTBTT)	0.01387	0.14638	0.09476
<b>3</b> (DTNTT)	0.01349	0.09040	0.14920
<b>4</b> (C <sub>10</sub> -DSeBTBT)	0.01349	0.08421	0.16017
<b>5</b> (DNTT)	0.01744	0.13024	0.13387
<b>6</b> (2,9-C <sub>1</sub> -DNTT)	0.01041	0.13842	0.07518
<b>7</b> (2,9-C <sub>10</sub> -DNTT)	0.01814	0.14215	0.12763
<b>8</b> (2,9-DPh-DNTT)	0.01605	0.14528	0.11046
<b>9</b> (BBTNDT)	0.01254	0.12400	0.10110
<b>10</b> (DBTTT)	0.00791	0.23875	0.03314
<b>11</b> (DTTE3)	0.01388	0.33602	0.04130
<b>12</b> (DTTE4)	0.01501	0.28635	0.05243
<b>13</b> (DN-TTF)	0.01259	0.40191	0.03131
<b>14</b> (BBBT)	0.00550	0.11578	0.04748
<b>15</b> (DBTTB)	0.00773	0.17784	0.04348
<b>16</b> (C <sub>12</sub> -BTBT)	0.01548	0.24285	0.06373
<b>17</b> (Hexacene)	0.02154	0.07679	0.28055
<b>18</b> (TTTTT)	0.02031	0.30588	0.06639
<b>19</b> (DTNN)	0.00929	0.20317	0.04572
<b>20</b> (DTNQ)	0.02249	0.22740	0.09891
<b>21</b> (BTAT)	0.01591	0.11420	0.13936



**Fig. S1** Ratio of averaged absolute value of transfer integrals ( $\langle |J| \rangle$ ) between the neighboring pairs in the morphology to reorganization energy ( $\lambda$ ) for the organic molecules used in this work.



**Fig. S2** Simple model containing grain (G) and grain boundary (GB), and corresponding equivalent circuits to represent electrical properties of organic semiconducting thin-film.  $R_G$ ,  $R_{GB}$ , and  $C_{GB}$  denote the electrical resistances of grain and grain boundary, and capacitance of grain boundary, respectively.

The full citation for reference 31 is:

M. J. Frisch, G. W. Trucks, H. B. Schlegel, G. E. Scuseria, M. A. Robb, J. R. Cheeseman, G. Scalmani, V. Barone, B. Mennucci, G. A. Petersson, H. Nakatsuji, M. Caricato, X. Li, H. P. Hratchian, A. F. Izmaylov, J. Bloino, G. Zheng, J. L. Sonnenberg, M. Hada, M. Ehara, K. Toyota, R. Fukuda, J. Hasegawa, M. Ishida, T. Nakajima, Y. Honda, O. Kitao, H. Nakai, T. Vreven, J. A. Montgomery, Jr., J. E. Peralta, F. Ogliaro, M. Bearpark, J. J. Heyd, E. Brothers, K. N. Kudin, V. N. Staroverov, R. Kobayashi, J. Normand, K. Raghavachari, A. Rendell, J. C. Burant, S. S. Iyengar, J. Tomasi, M. Cossi, N. Rega, J. M. Millam, M. Klene, J. E. Knox, J. B. Cross, V. Bakken, C. Adamo, J. Jaramillo, R. Gomperts, R. E. Stratmann, O. Yazyev, A. J. Austin, R. Cammi, C. Pomelli, J. W. Ochterski, R. L. Martin, K. Morokuma, V. G. Zakrzewski, G. A. Voth, P. Salvador, J. J. Dannenberg, S. Dapprich, A. D. Daniels, Ö. Farkas, J. B. Foresman, J. V. Ortiz, J. Cioslowski, and D. J. Fox, Gaussian 09, Revision E.01, Gaussian, Inc., Wallingford CT, 2009.